



**PATENTS** 

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TRADE WINTED STATES PATENT AND TRADEMARK OFFICE

Applicant(s)

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Examiner: Savitri Mulpuri

Serial No.:

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Art Unit: 1665

Filed:

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Docket: YOR920010308US1 (16315)

For: EPITAXIAL AND POLYCRYSTALLINE

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Dated: March 12, 2003

GROWTH OF Si<sub>1-x-y</sub>GE<sub>x</sub>C<sub>y</sub> AND Si<sub>1-y</sub>C<sub>y</sub> ALLOY LAYERS ON Si By UHV-CVD

Commissioner for Patents Washington, DC 20231

## **AMENDMENT AND RESPONSE**

Sir:

In response to the Office Action dated December 12, 2002, applicants submit the following amendments and remarks for entry of record in the above-identified patent application.

## **IN THE CLAIMS**:

Please cancel Claims 4, 6, 1/7 and 18, without prejudice or disclaimer, and please amend
Claims 1, 12, 13, 14, 27 and 28 to read as follows:

1. (Amended) A method for forming an alloy layer of silicon carbon on a

CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents and Trademarks, Washington, D.C. 20231 on March 12, 2003.

Dated: March 12, 2003

Amet Grossman